

*Amendment to the Specification*

Please amendment the specification as follows:

[0023] While the diffraction element is described in relation to being in an illumination system of a lithography tool, as will be understood by one of ordinary skill in the art, the diffraction element can be used in any system employing light in the short wavelength range (e.g., about 100 nm to about 300 nm), such as a holography system, a metrology system, an illumination system, or the like. Also, it is to be appreciated that although described as being a diffraction grating on a substrate, the diffraction grating can be added to any optical element within an optical system, for example a grating 1400 on a lens 1402 in FIG. 14 or a grating 1500 a mirror 1502 in FIG. 15, without departing from the scope of the present invention.

After paragraph [0018] please insert the following paragraph:

FIGS. 14 and 15 show various examples of optical devices including gratings, according to various embodiments of the present invention.